Long-lasting hydrophobization of monolithic phenolic gels via silulation

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- Aerogels and xerogels based on resorcinol-formaldehyde (RF) polymers have promising properties for applications as filters or catalysts^[1]
- However, free OH groups of the phenolic gels make them hydrophilic
- Previous publications include post-synthetic silylation of RF gels, but only on powdered materials using small silyl reagents^[2-3]
- Our approach is to functionalize monolithic RF xerogels, more specifically to silulate them with sterically demanding silulation reagents to create a long-lasting hydrophobicity

placement of water droplet unmodified RF xerogel absorbs RF xerogel water

- Silylation using polar aprotic solvents
- Addition of external base

Sample

TMS-A

TMS-B

TBS-A

TIPS-A

TIPS-B

TBDPS-A

Si Content

[%] (m/m)

0.61

1.16

1.51

0.20

0.27

1.23

Synthesis of silvlated RF xerogels

Motivation



- Use of sterically demanding silulating reagents
- Variation of Si-counterion (electronically activated triflate)

Sample	Silyl Reagent	Base
TMS-A	Trimethylsilyl chloride (TMS-Cl)	Imidazole
TMS-B	Trimethylsilyl triflate (TMS-OTf)	2,6-lutidine
TBS-A	tertButyldimethylsilyl chloride (TBS-Cl)	Imidazole
TIPS-A	Triisopropylsilyl triflate (TIPS-OTf)	Imidazole
TIPS-B	Triisopropylsilyl chloride (TIPS-Cl)	2,6-lutidine
TBDPS-A	tert Butyldiphenylsilyl chloride (TBDPS-Cl)	Imidazole

XPS analysis



- Successful incorporation of silicon
- Silicon is present in quantities < 2 % by weight
 - > Not all free hydroxy groups were silvlated
 - > Chemical reactivity of the phenolic hydroxyl groups in the gel does not seem to be crucial, but rather their accessbility within the pore network

XPS-analysis

- Resulting bond energies clearly indicate the presence of silicon-oxygen bonds
- Ratio of Si-O bonds to Si-C bonds correspond to expected 1:3 ratio for trialkylsilyl ethers
 - Formation of covalent Si-O bonds

SEM-EDX-Characterization

SEM-EDX images of an RF xerogel treated with TBS-A homogeneous distribution of carbon, oxygen and silicon

SEM-EDX analysis



Survey C 1s hv = 1486.7 eV hv = 1486.7 eV C-C C-0 C-Si C=0 200 284 400 294 292 290 288 286 282 Binding energy [eV] Binding energy (eV) O 1s Si 2p hv = 1486.7 eV hv = 1486.7 eV 0-C O-Si Si_O

Experimental



> The lower relative abundance of Si agrees with the hypothesis that not all phenolic hydroxy groups are silylated



Results Ø **Characterization**



SEM analysis

RF-TBS-A

Microstructural	properties

- Pycnometry revealed slight reduction in porosity for silvlated samples
- > the pore network is not significantly affected by the functionalization process, nor the porous network within the xerogel

	Density	[g·cm⁻³]	Porositv	Inner Surface Area		
Sample	Envelope	Skeletal	[%]	[m ² ·g ⁻¹]		
RF	0.3262	1.4453	77.39	0.676 ± 0.003		
RF-TMS-B	0.3213	1.3545	76.28	0.411 ± 0.044		
RF-TIPS-B	0.3239	1.3685	76.33	0.423 ± 0.008		

Determination of wetting behavior



• The monoliths in water and 10% aq. HCl were more inert between the silylated variants compared to the RF reference, except for RF-

	time exposed to air / months							
	1	2	3	4	5	8	11	
sample			contact angle [°]					
RF				n.a.				
RF-TMS-A				n.a.				
RF-TMS-B	139.5±1.8 (147.5±0,7)	137.2±2.9 (143.0±1.1)	136.5±3.7 (137.1±0.7)	135.7±3.4	n. d.	n. d.	n. d.	
RF-TBS-A	136.4±3.0 (140.0±2.9)	136.5±1.5 (142.1±1.0)	135.4±2.1 (142.9±2.5)	135.3±2.4	135.0±1.1	134.5±1.5	134.2±1.3	
RF-TIPS-A	142.8±1.2	n. d.	142.6±1.7	n. d.	141.1±2.2	137.9±1.9	136.9±1.9	
RF-TIPS-B	143.7±2.0 (151.1±1.1)	143.9±0.4 (149.9±0.6)	140.5±1.8 (146.6±1.7)	139.1±1.3	n. d.	n. d.	n.d.	
RF-TBDPS-B	138.3±2.2	n. d.	139.3±3.2	n. d.	139.2±2.2	135.1±1.8	133.9±2.5	

Static contact angles, as determined using tangent or the LB-ADSA (in brackets) method

Dynamic contact angles, as determined using Wilhelmy method

time exposed to air / months

	1	2	3	4	5	8	11	
sample		contact angle [°]						
RF				n.a.				
RF-TMS-A				n.a.				
RF-TMS-B	152.4±1.4	144.9±12.3	143.6±13.0	144.0±1.1	n. d.	n. d.	n. d.	
RF-TBS-A	123.8±15.9	121.6±2.4	123.4±12.8	124.3±2.0	136.1±1.7	132.3±2.9	125.3±16.5	
RF-TIPS-A	151.9±8.3	n. d.	150.1±7.4	n. d.	146.2±4.8	132.2±2.4	129.8±2.3	
RF-TIPS-B	139.1±8.0	137.9±4.0	138.0±1.9	137.4±1.4	n. d.	n. d.	n. d.	
F-TBDPS-B	101.8±11.3	n. d.	112.5±17.1	n. d.	120.0±6.4	112.8±10.7	119.2±5.9	
		n 2	- not applicable	o (droplot was	beerbed by me	nalith), nd - n	at datarminad	

n.a. = not applicable (droplet was absorbed by monolith); n.d. = not determined Static and dynamic contact angles

- Static contact angles between sample surface and water droplet (tangent method): 133.9 - 143.9°
- Automatized positioning of the tangent using low-bond axisymmetric drop shape analysis (LB-ADSA) consistently results in higher values (137.1 - 151.1°)
- Contact angles determined by Wilhelmy method in range of 101.8 152.4°
- > A procedure for the silulation of monolithic resorcinol-formaldehyde xerogels has been established
- > Sterically and electronically varied silyl reagents including electronically activated triflates could be applied in solution phase using auxiliary amines as external base
- onclusion Xerogels displayed marked hydrophobicity with contact angles consistently exceeding 130°
 - > The hydrophobic properties remained when the monoliths are exposed to humid air for several months
- > RF gels with sterically demanding silyl groups sustained water and even dilute hydrochloric acid for weeks^[4] U



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